

1                   What is claimed is:

2   **[01]** An architecture for the measurement of photomask optical path difference, comprising:

3           A spatially coherent light source;

4           An interferometric beam processing module;

5           An optical microscope; and

6           A photosensitive detector;

7           Wherein said module is disposed to receive and divide light from said light source into a

8                   number of phase-coherent light beams, each of which passes through a separate

9                   aperture;

10          Wherein said microscope is disposed to image the multitude of said apertures in said

11                   module with a given demagnification onto a photomask; and

12          Wherein said detector is disposed to record transmitted fringe intensity.

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14   **[02]** The apparatus of claim 1 wherein said light source is a laser with a wavelength that is

15          approximately the same as the actinic wavelength of said photomask.

16   **[03]** The apparatus of claim 1 wherein said optical demagnification of said apertures is greater

17          than 50.

18   **[04]** The apparatus of claim 1 wherein said module is of the Mach-Zehnder (MZ)

19          interferometer type.

20   **[05]** The apparatus of claim 1 wherein the relative optical phase between said phase-coherent

21          light beams may be varied by suitable adjustments to said interferometric beam module.

22   **[06]** The apparatus of claim 1 wherein said module is a dual-aperture screen.

- 1   **[07]** The apparatus of claim 1 wherein said module contains mirrors are fabricated using the  
2   techniques of micro-electrical and mechanical system (MEMS).
- 3   **[08]** The apparatus of claim 1 wherein said detector is a UV-sensitive CCD camera.
- 4   **[09]** The apparatus of claim 1 wherein said detector is a photomultiplier tube (PMT).
- 5   **[10]** The apparatus of claim 1 wherein the number of said apertures and said phase-coherent  
6   light beams is two (2).
- 7   **[11]** An architecture for the measurement of photomask optical path difference, comprising:  
8       A spatially coherent light source;  
9       An interferometric beam processing module;  
10      An optical microscope; and  
11      A photosensitive detector;  
12      Wherein said module is disposed to receive and divide the light from said light source  
13          into a number of phase-coherent light beams, each of which passes through a  
14          separate aperture;  
15      Wherein said microscope is disposed to image the multitude of said apertures in said  
16          module with a given demagnification onto a photomask; and  
17      Wherein said detector is disposed to record reflected fringe intensity
- 18   **[12]** The apparatus of claim 11 wherein said light source is a laser with a wavelength that is  
19   approximately the same as the actinic wavelength of said photomask.
- 20   **[13]** The apparatus of claim 11 wherein said optical demagnification of said apertures is  
21   greater than 50.
- 22   **[14]** The apparatus of claim 11 wherein said module is of the Mach-Zehnder (MZ)  
23   interferometer type.

- 1    **[15]** The apparatus of claim 11 wherein the relative optical phase between said phase-coherent  
2    light beams may be varied by suitable adjustments to said interferometric beam module.
- 3    **[16]** The apparatus of claim 11 wherein said module is a dual-aperture screen.
- 4    **[17]** The apparatus of claim 11 wherein said module contains mirrors are fabricated using the  
5    techniques of micro-electrical and mechanical system (MEMS).
- 6    **[18]** The apparatus of claim 11 wherein said detector is a UV-sensitive CCD camera.
- 7    **[19]** The apparatus of claim 11 wherein said detector is a photomultiplier tube (PMT).
- 8    **[20]** The apparatus of claim 11 wherein the number of said apertures and said phase-coherent  
9    light beams is two (2).

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